



Dephasing in Strongly Anisotropic Black Phosphorus

Francesca Telesio

Modena, 20/03/2017



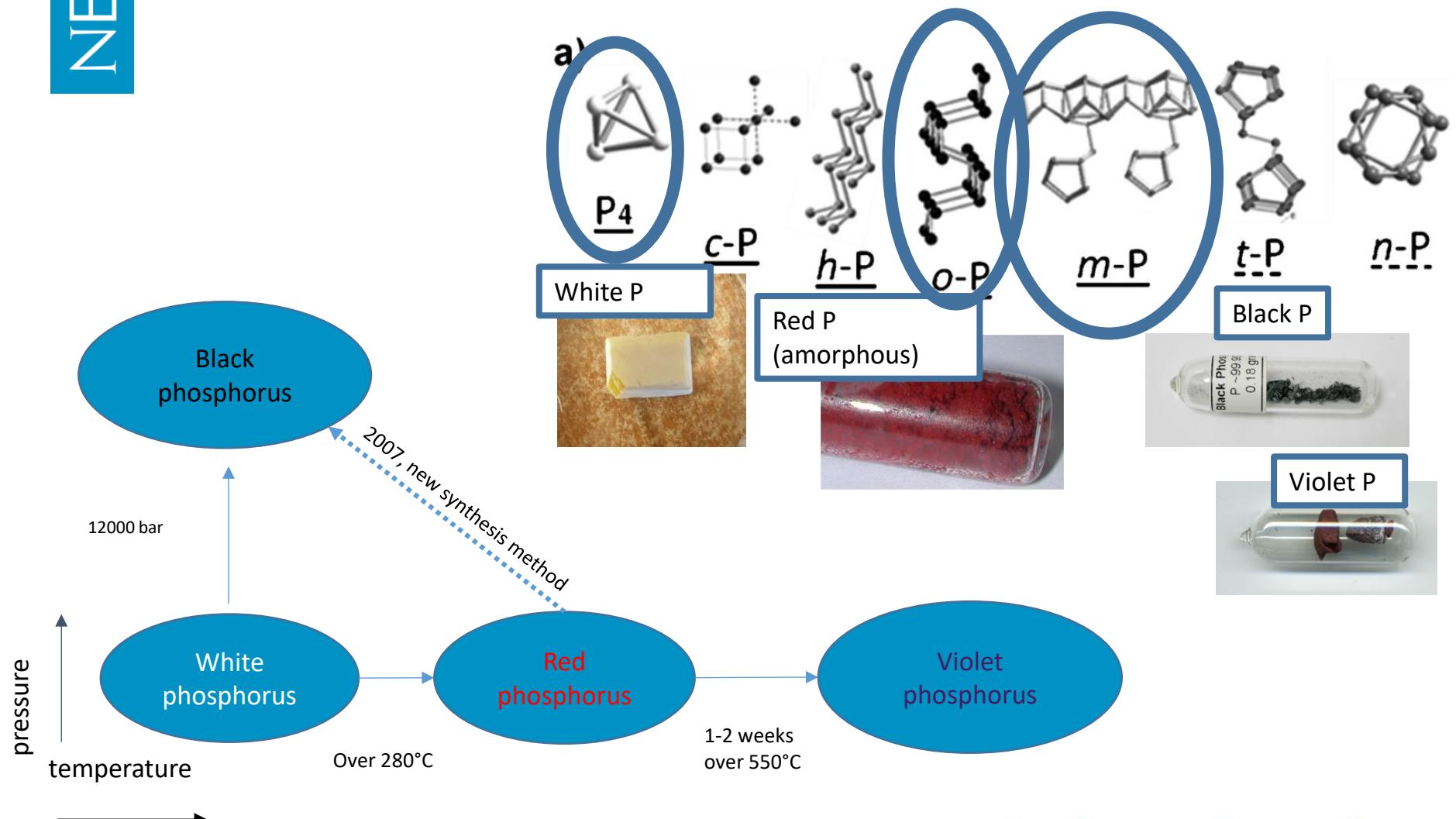
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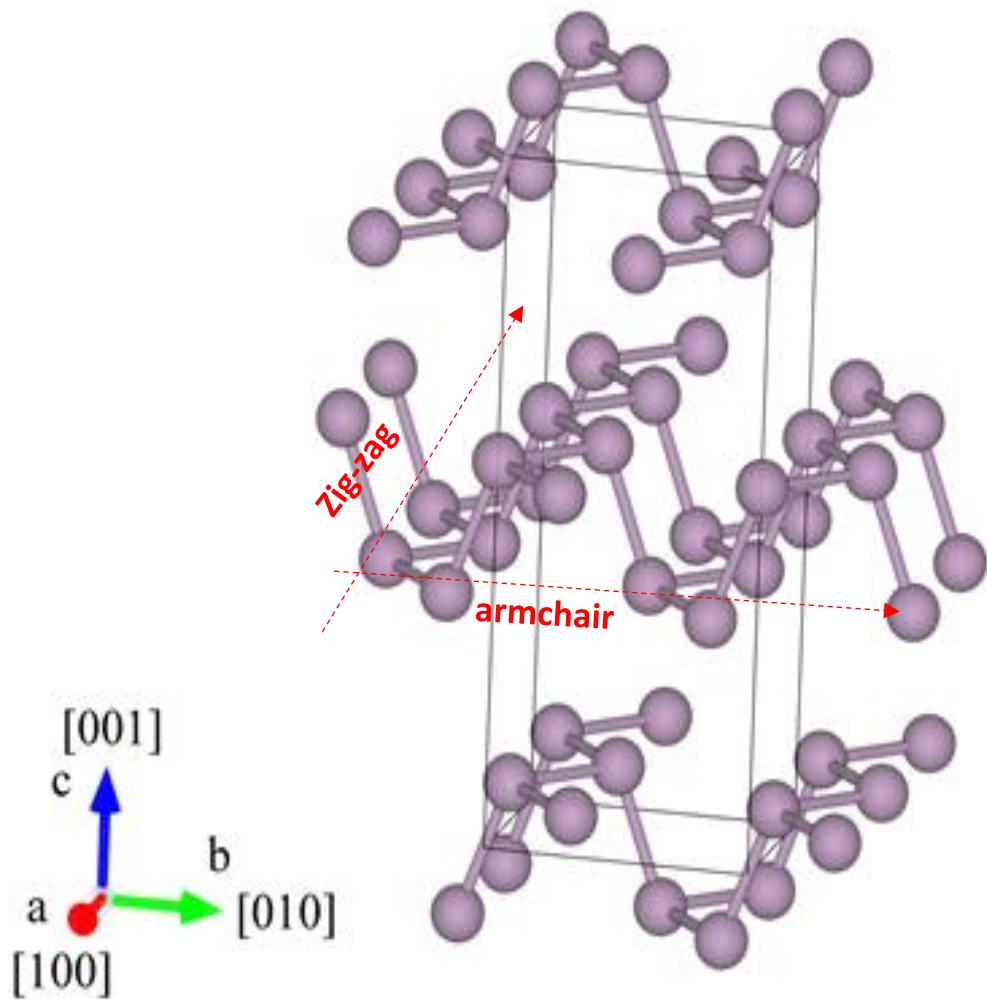
Summary

- Introduction: black Phosphorus
- Dephasing in black Phosphorus
 - Weak localization measurements
 - Data analysis and interpretation
 - Conclusions
- Outlooks: SEED project – STM on few-layer black Phosphorus

The family of phosphorus alloys

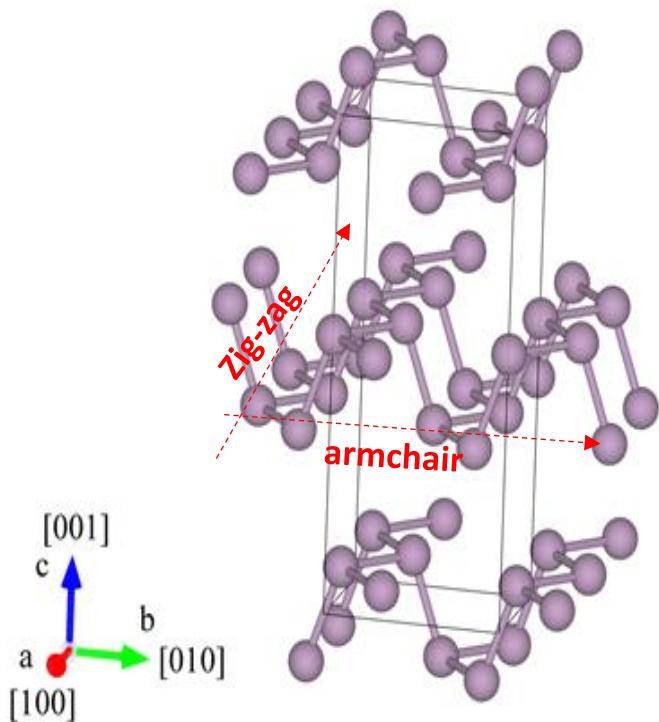


Black phosphorus



Cell parameters
 $a=3.13\text{\AA}$
 $b=10.47\text{\AA}$
 $c=4.37\text{\AA}$

Black phosphorus

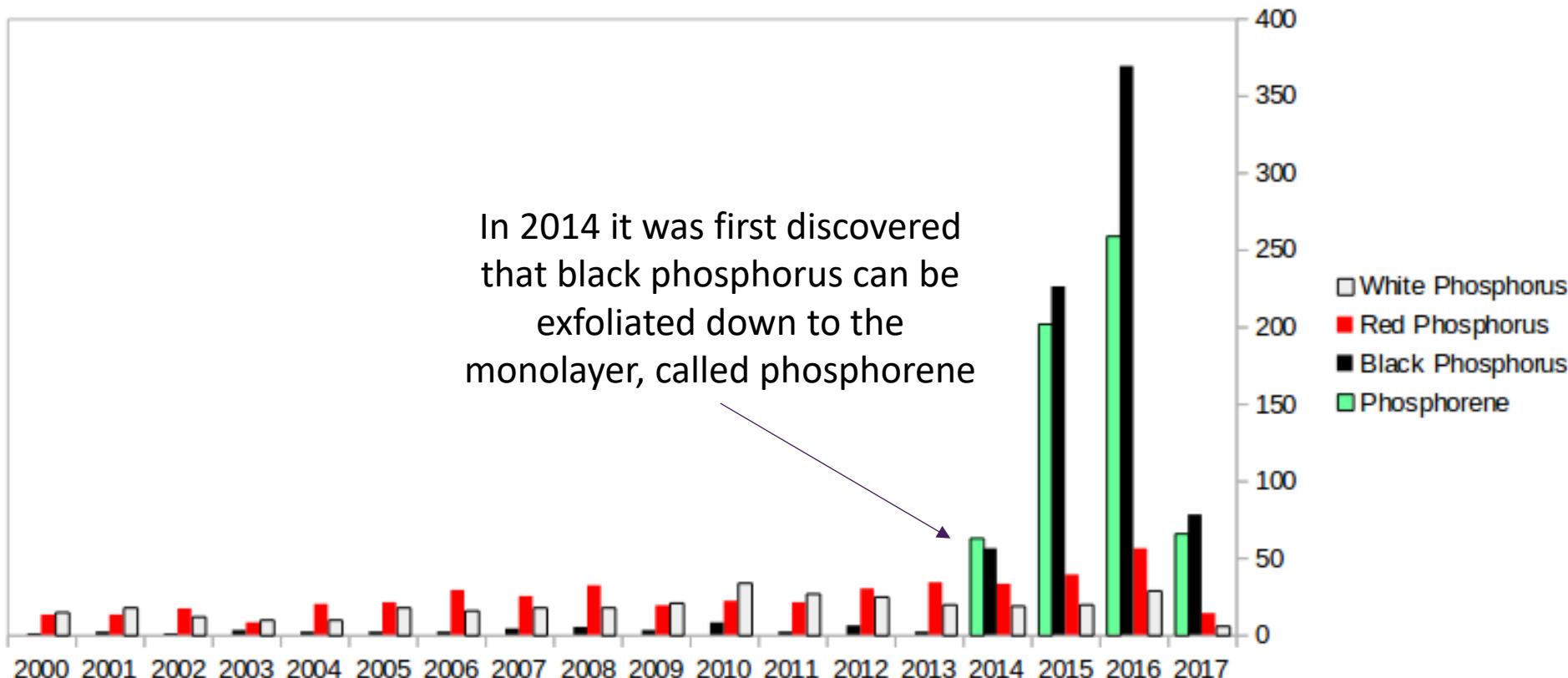


Cell parameters
 $a=3.13\text{\AA}$
 $b=10.47\text{\AA}$
 $c=4.37\text{\AA}$

- ✓ In 1914 first successful synthesis (Bridgman) and in 2007 synthesis at room pressure (Lange, Nilges)
- ✓ p-type semiconductor: 0.3eV direct band gap and high hole mobility (64,000 cm^2/Vs @ 20 K)
- ✓ 1983 (Narita): n-type doping by Te

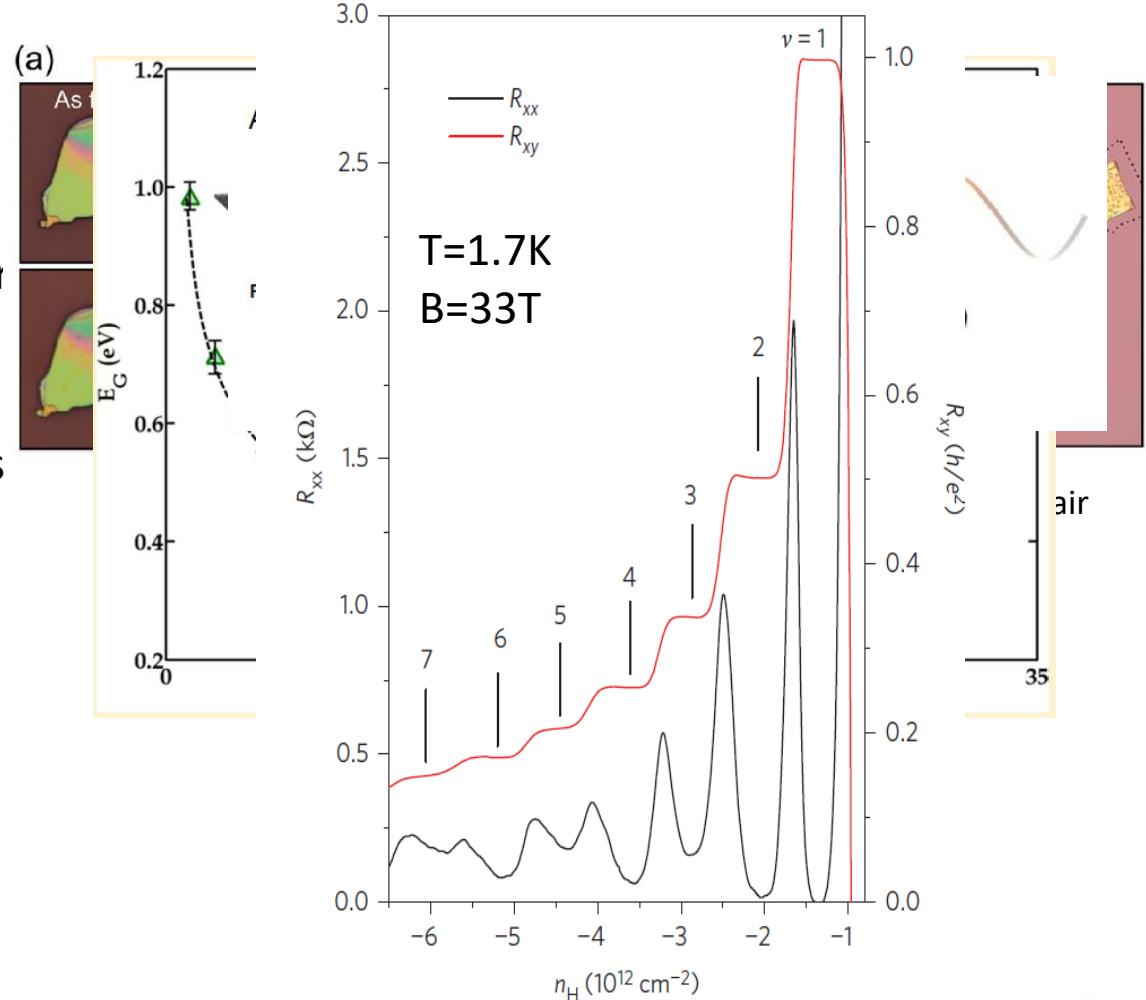
The Renaissance of Black Phosphorus

In 2014 it was first discovered that black phosphorus can be exfoliated down to the monolayer, called phosphorene



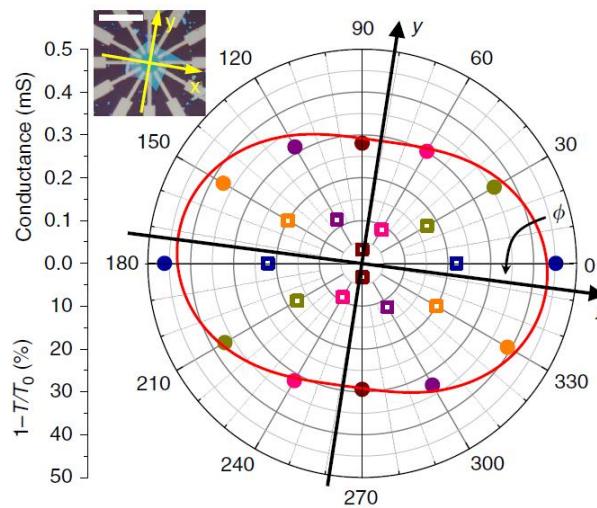
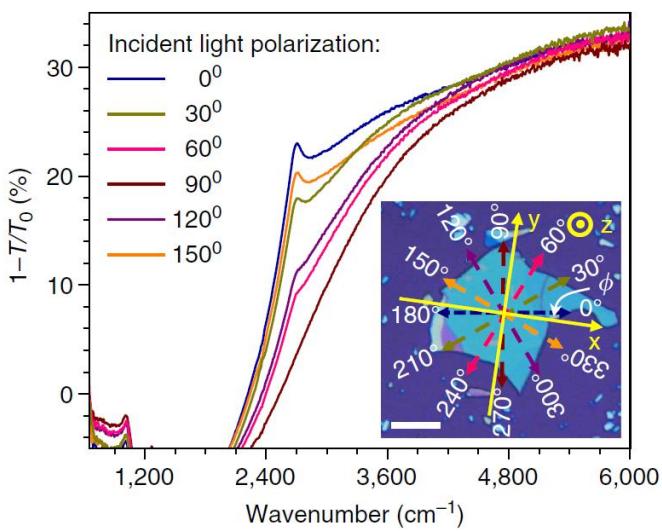
The renaissance of black phosphorus

- ✓ Highly reactive in air
- ✓ Direct band gap
- ✓ Band-gap tunable with layer number
- ✓ And much more... such as some recent measurements of quantum Hall effect at high field

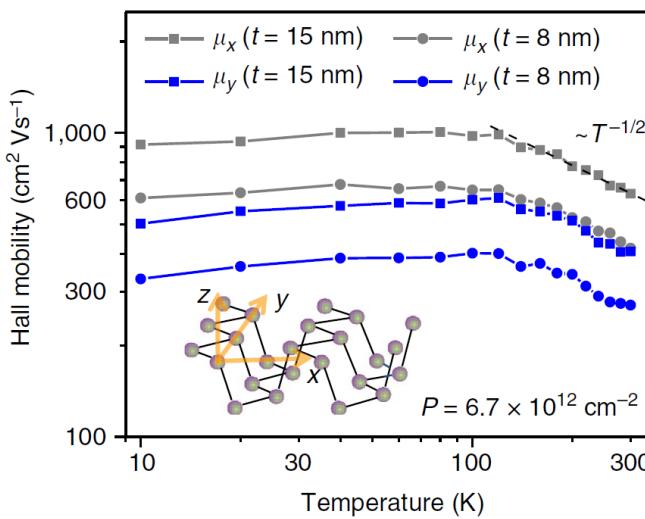


The reinassance of black phosphorus

✓ In-plane anisotropy of optical and transport properties

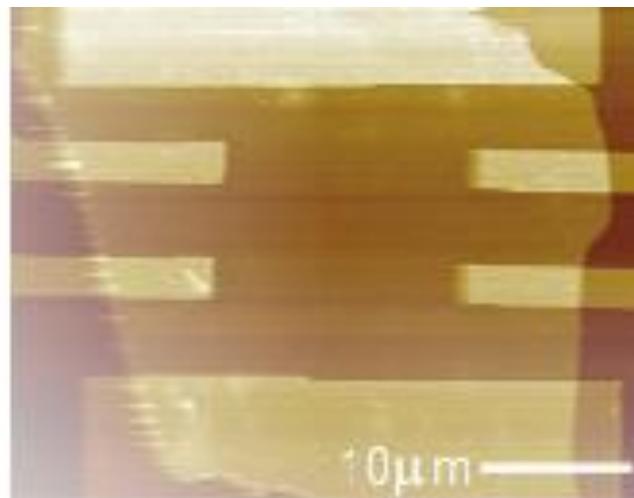
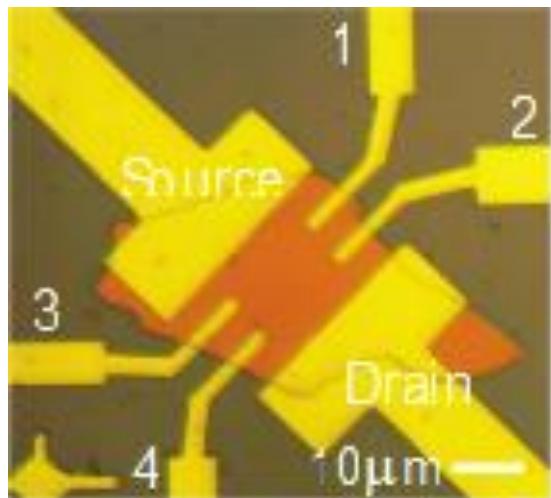
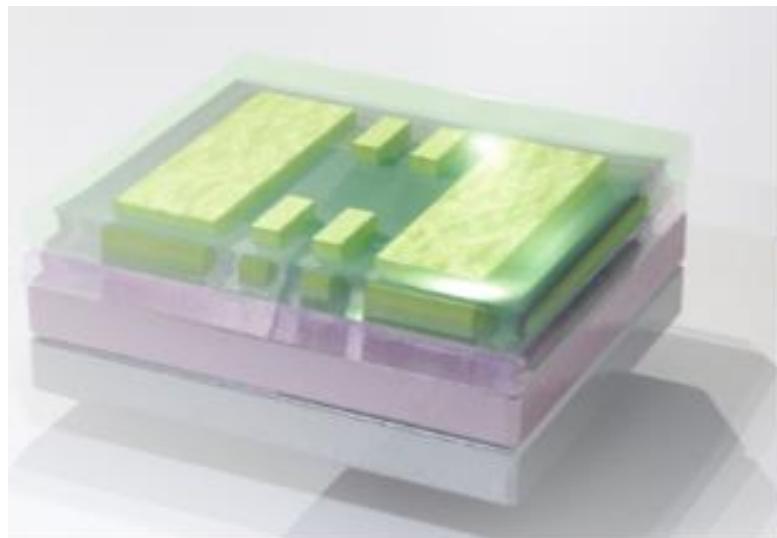
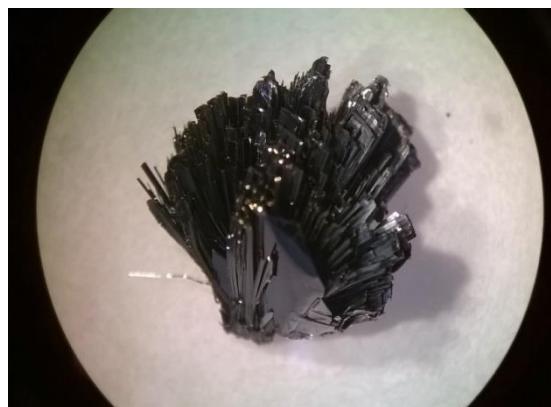


$$\sigma_x/\sigma_y \approx 1.5$$



$$\mu_x/\mu_y \approx 1.8$$

bP Field Effect Transistor

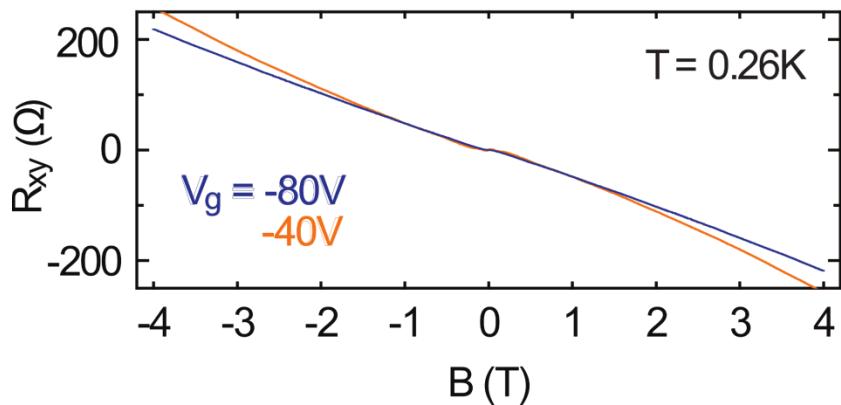
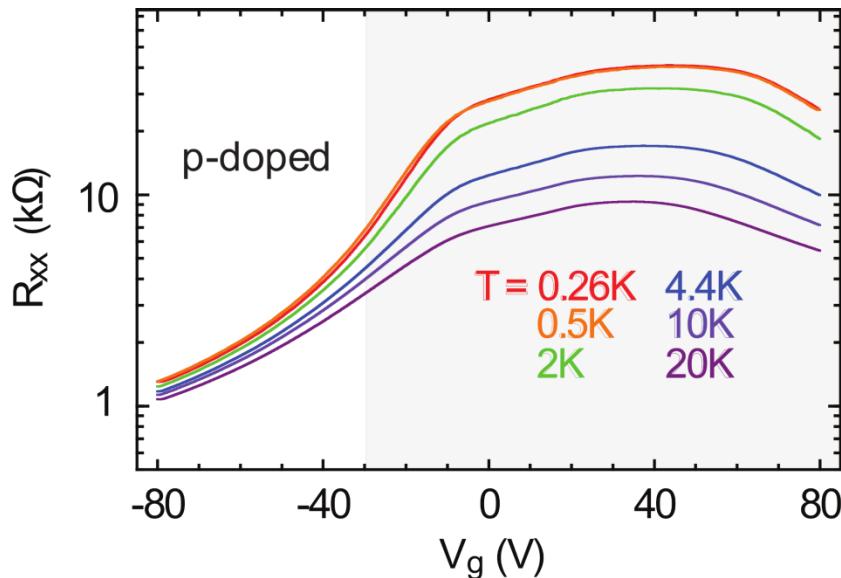


PMMA
MMA
Ti/Au contacts
bP flake
HMDS
 SiO_2 thermal oxide
Si

R_{xx} : 1-2
 R_{xy} : 1-3

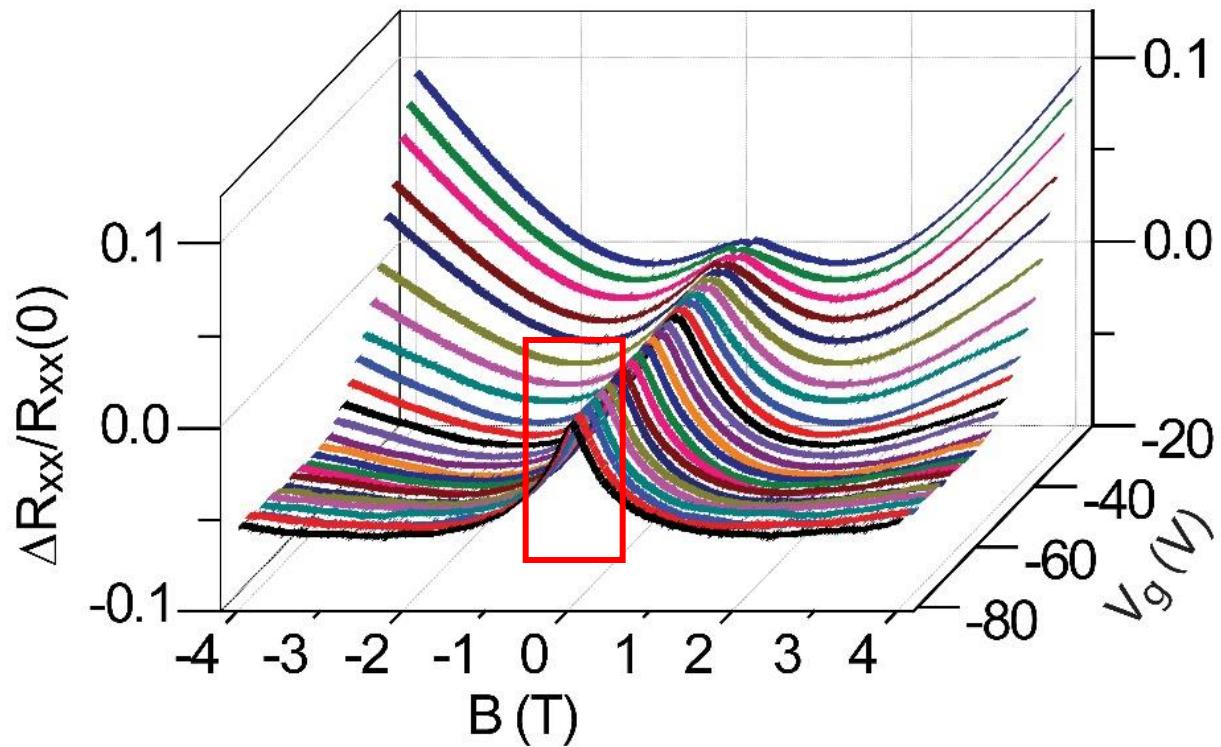
Flake thickness:
 $65 \pm 2 \text{ nm}$

Transport Characterization



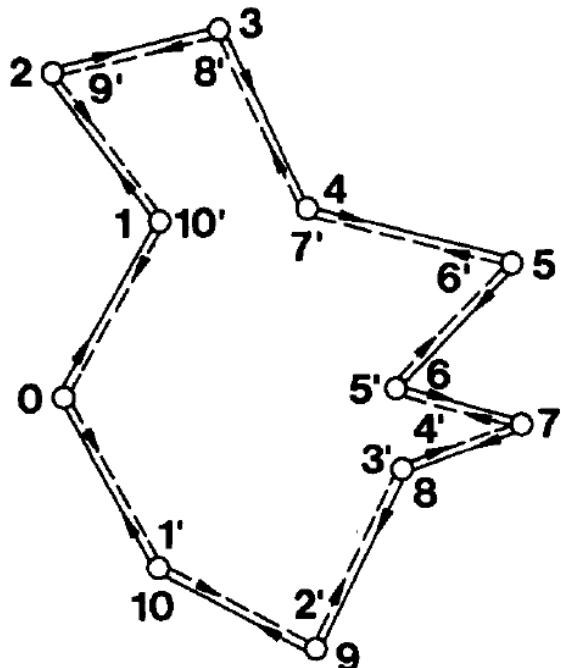
- p type for $V_g < -30$ V
- $p = 10^{13} \text{ cm}^{-2}$ for $V_g = -30$ V
- Field-effect mobility μ :
300 cm²/Vs at $V_g = -70$ V
- Negligible T-dependence in μ for $0.26 \text{ K} < T < 20 \text{ K}$

Longitudinal magnetotransport measurements



Weak Localization

Weak localization is a quantum effect related to coherent scattering at low temperatures.



Normal Diffusion Model:

$$P = |A_1|^2 + |A_2|^2 = 2 |A|^2$$

Coherent Addition:

$$P = |A_1 + A_2|^2 = |2A|^2 = 4 |A|^2$$

Since weak localization is a coherent scattering effect:

- It's depressed by magnetic field
- It's smeared by temperature

Picture from Bergmann, Weak localization in thin films, Physics Reports 107, 1984

Weak Localization: Hikami-Larkin-Nagaoka model

$$\Delta \sigma = -\frac{e^2}{2 \pi^2 \hbar} \left(\Psi\left(\frac{1}{2} + \frac{B_1}{B}\right) - \frac{3}{2} \Psi\left(\frac{1}{2} + \frac{B_2}{B}\right) + \frac{1}{2} \Psi\left(\frac{1}{2} + \frac{B_3}{B}\right) \right)$$

Where Ψ is the digamma function

$$B_1 = \cancel{B_0} + \cancel{B_{so}} + \cancel{B_s}$$

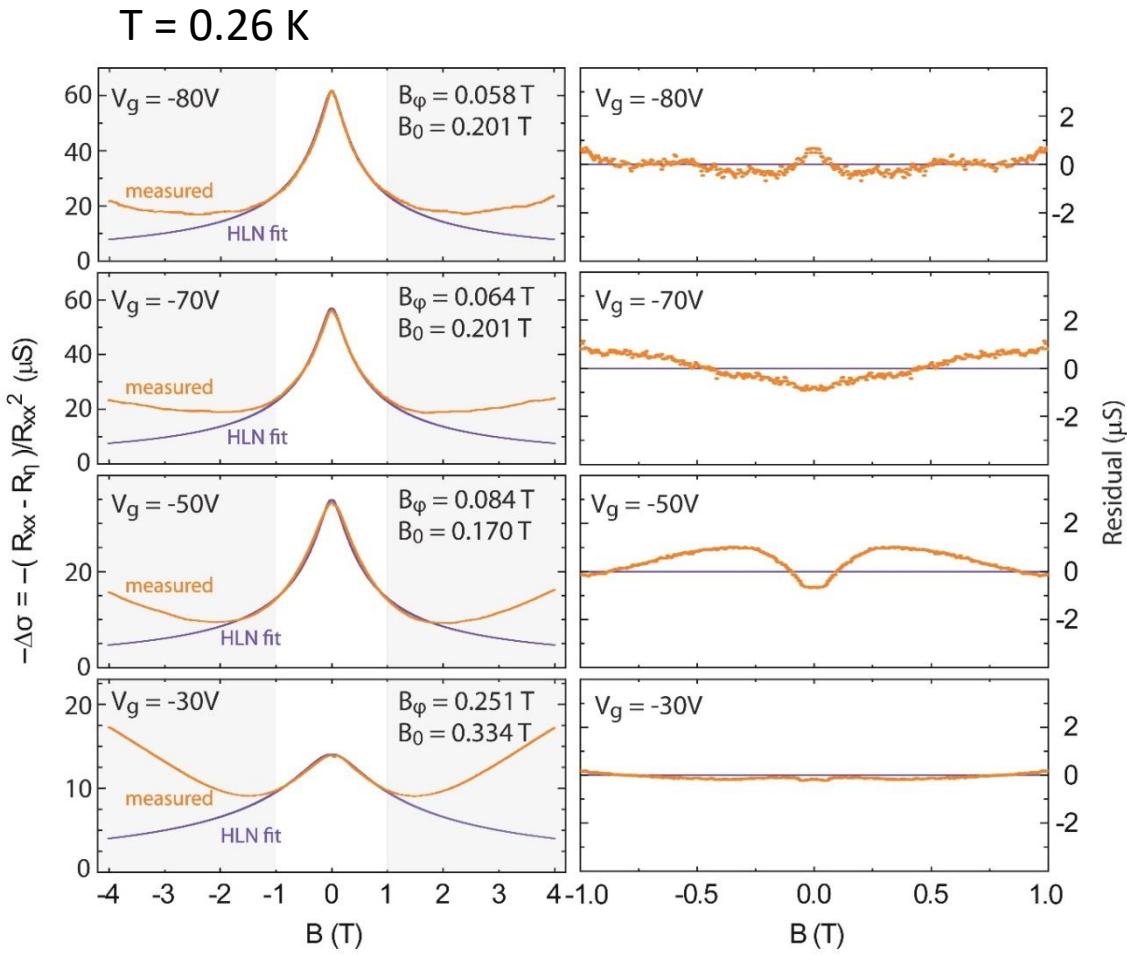
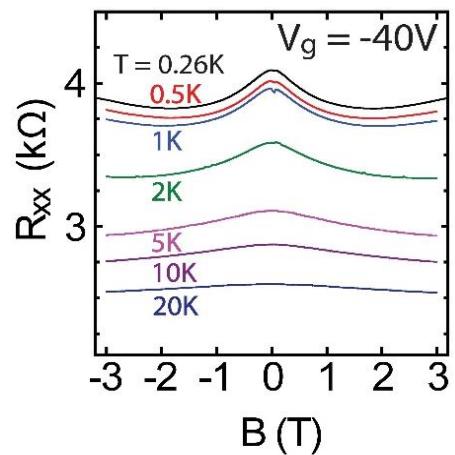
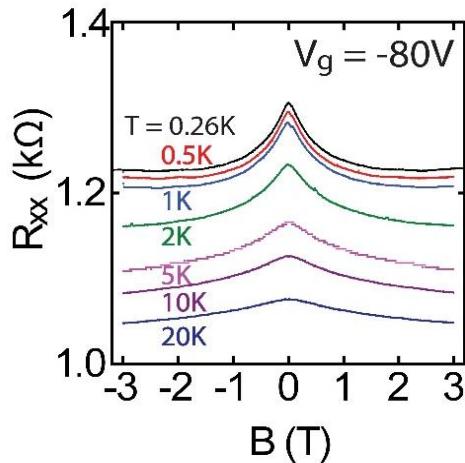
$$B_2 = \cancel{\frac{4}{3}B_{so}} + \cancel{\frac{2}{3}B_s} + \cancel{B_\phi}$$

$$B_3 = \cancel{2B_s} + B_\phi$$

S. Hikami, A. I. Larkin, and Y. Nagaoka,
Prog. Of Theor. Phys. 63 (1980) 707.

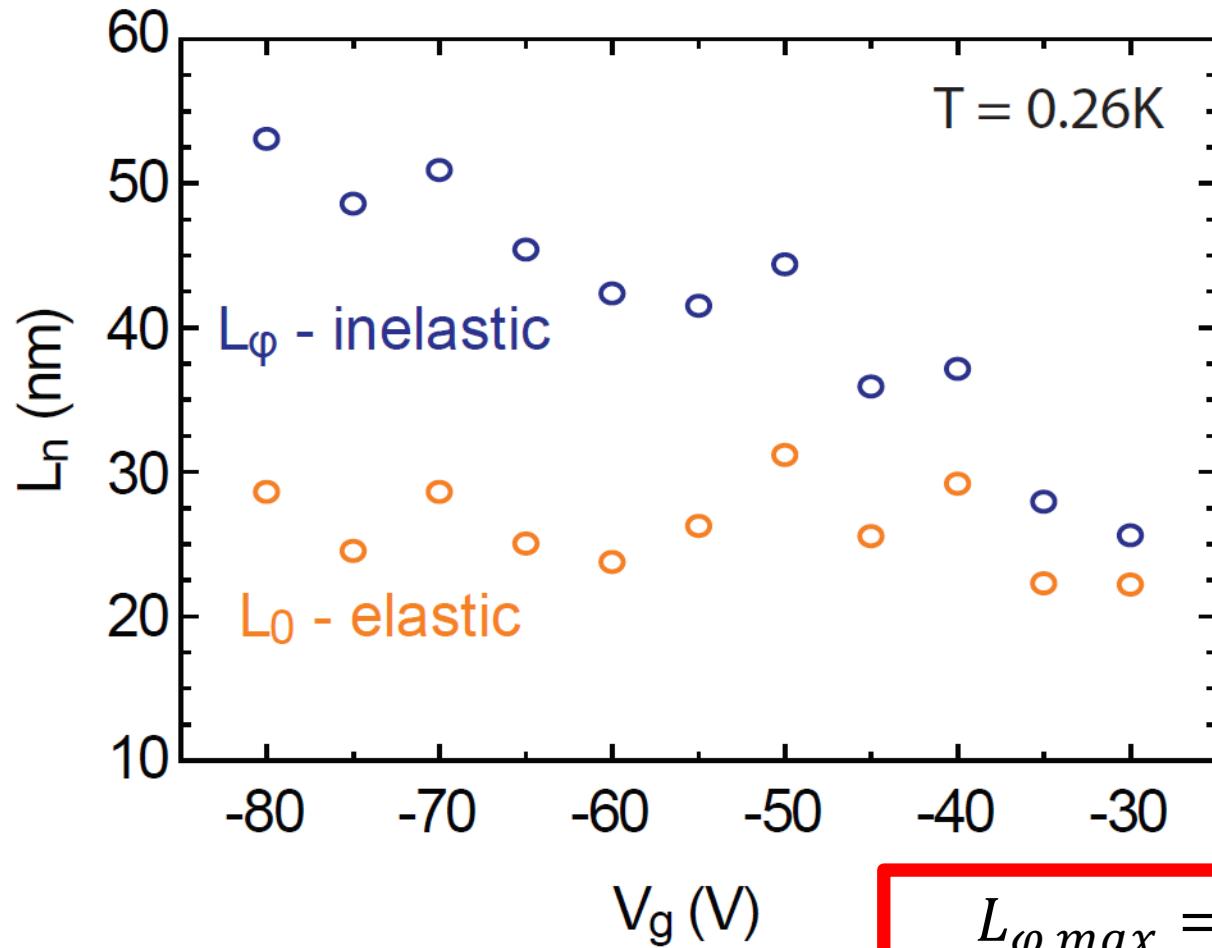
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Weak Localization



Scattering Lengths

$$BL^2 = h/4e$$



$L_{\phi,max} = 55 \text{ nm}$

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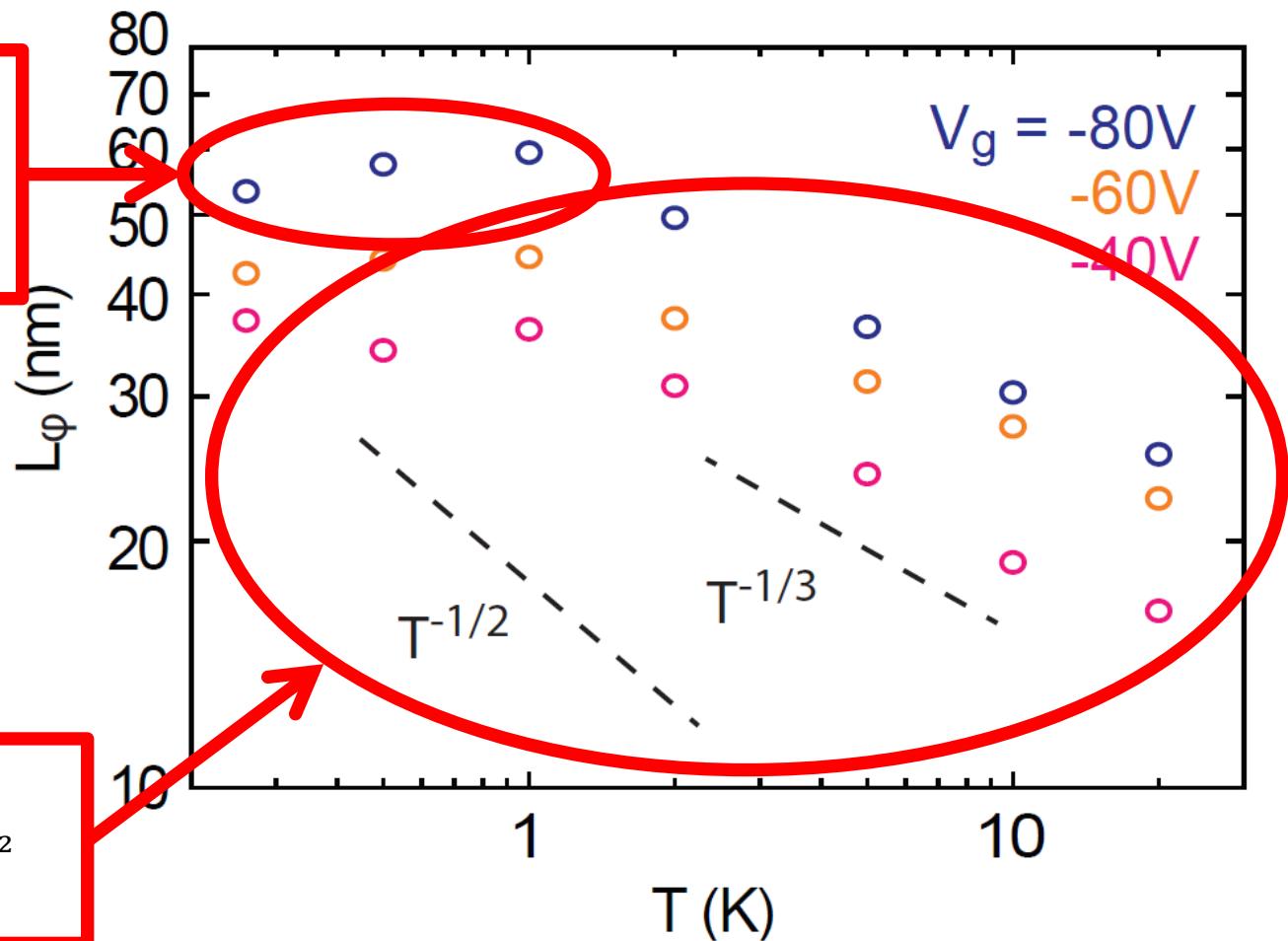
Scattering Lengths

- Dephasing length vs. inelastic scattering time:
 $L_\varphi = \sqrt{D\tau_\varphi}$ with D diffusion coefficient
- Ballistic transport: $\tau_\varphi \propto T^{-2}$ or $L_\varphi \propto T^{-1}$
- Diffusive transport ($L_0 < L_\varphi$):

$$\tau_\varphi \propto T^{-1} \text{ or } L_\varphi \propto T^{-1/2}$$

Scattering Lengths

Saturation most likely due to impurities.



L_ϕ does not follow a $T^{-1/2}$ behaviour.

Quasi-1D systems

VOLUME 86, NUMBER 9

PHYSICAL REVIEW LETTERS

26 FEBRUARY 2001

Geometry-Dependent Dephasing in Small Metallic Wires

D. Natelson, R. L. Willett, K. W. West, and L. N. Pfeiffer

Bell Laboratories, Lucent Technologies, Murray Hill, New Jersey 07974

(Received 19 June 2000)

Temperature dependent weak localization is measured in metallic nanowires in a previously unexplored size regime down to width $w = 5$ nm. The dephasing time, τ_ϕ , shows a low temperature T dependence close to quasi-1D theoretical expectations ($\tau_\phi \sim T^{-2/3}$) in the narrowest wires, but exhibits a relative saturation as $T \rightarrow 0$ for wide samples of the same material as observed previously. As only sample geometry is varied to exhibit this constraint on models of dephasing

PHYSICAL REVIEW B, VOLUME 64, 121404(R)

Phase-coherent transport in ropes of single-wall carbon nanotubes

J. Appenzeller, R. Martel, and Ph. Avouris

IBM T. J. Watson Research Center, Yorktown Heights, New York 10598

H. Stahl, U. Th. Hunger, and B. Lengeler

II. Physikalisches Institut, RWTH Aachen, Templergraben 55, 52056 Aachen, Germany

(Received 21 May 2001; revised manuscript received 23 July 2001; published 6 September 2001)

To study the phase breaking scattering events in single-wall carbon nanotubes (SWNTs), ropes of SWNTs are intentionally damaged by Ar^+ ion milling. Due to this treatment, the average distance an electron can travel before being elastically scattered is reduced to about 10 nm. This significantly increases the probability of one-dimensional localization and allows us to obtain the phase coherence length (L_Φ) in ropes of SWNTs as a function of temperature. We find that Nyquist scattering ($\tau_\Phi \sim T^{-2/3}$) as well as another dephasing mechanism with a $\tau_\Phi \sim T^{-1}$ dependence are involved in limiting the phase-coherent transport. We also investigate the scattering of hot electrons in the system. The results support the statement that two different scattering mechanisms dominate the phase coherence length for different rope samples.

Comparison with quasi-1D wires

D. Natelson et al.
PRL 86 (2009):

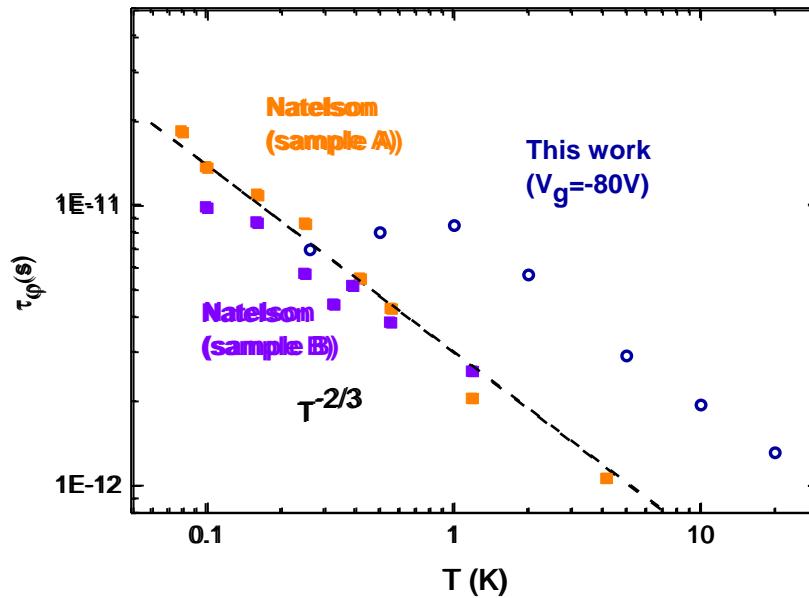
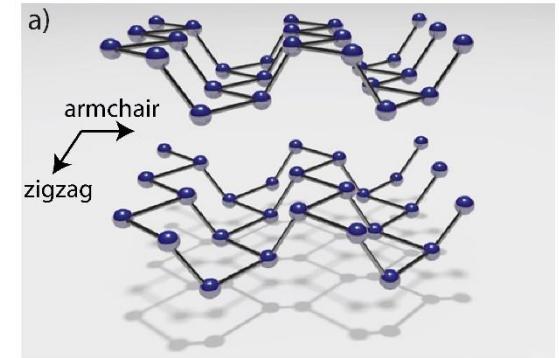
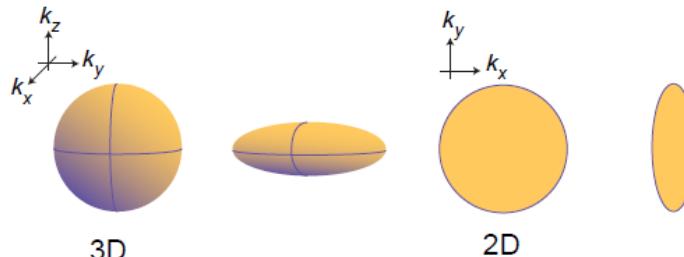
quasi-1D:

$$L_\varphi, L_T > w, t$$

width w
thickness t

$$\tau_\varphi \propto T^{-2/3}$$

$$L_\varphi \propto T^{-1/3}$$



$$L_\varphi = 55 \text{ nm}$$

thermal length:

$$L_T = \sqrt{\hbar D / k_B T} \\ = 10 - 60 \text{ nm}$$

Conclusions...

- ✓ Weak localization observed in a bP FET
- ✓ Excellent agreement with HLN model
- ✓ Dephasing length L_φ reaches 55 nm
- ✓ T-dependence of L_φ close to quasi-1D
- ✓ This is a further proof of strong in plane anisotropy of bP

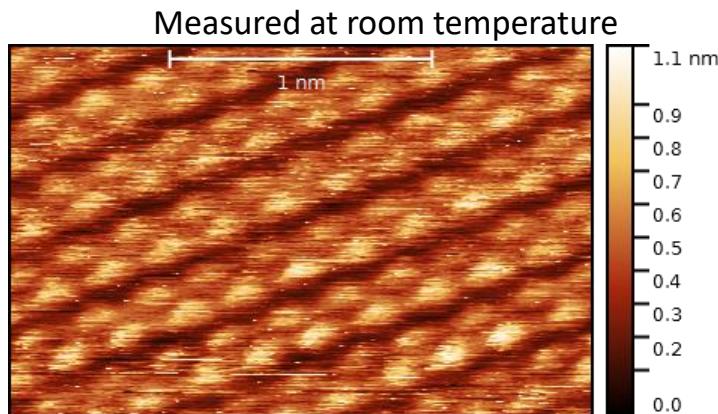
...and outlooks

SEED Project SURface properties of few layer black PHOSphorus investigated by scanning tunnelling microscopy

- Clean surface of few-layer bP
 - On graphene on SiC
 - On Si/SiO₂
- Study of point defects
- Functionalization of the surface by metal evaporation

... and outlooks

Ongoing activity: Atomic Resolution on few-layer bP



Measured unit cell parameter
 $a = 3.86 \text{ \AA}$, $c = 4.27 \text{ \AA}$

Measured parameters are in very close
agreement to the reported and predicted values



C. D. Zhang et. al. J. Phys. Chem. C 2009, 113, 18823.
 Morita, A et. al. Appl. Phys. A: Mater. Sci. Proc. 1986, 39, 227.

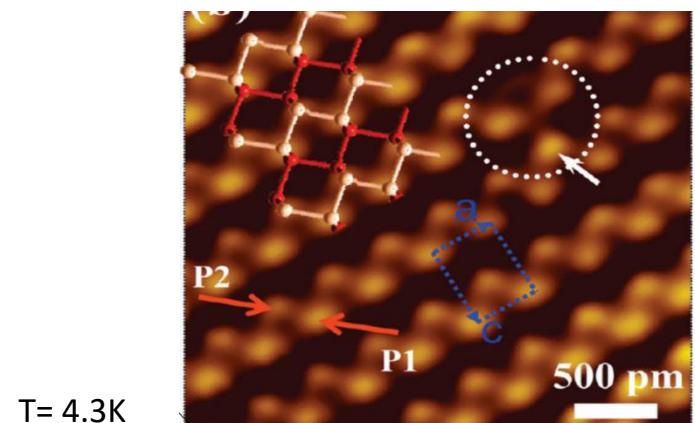


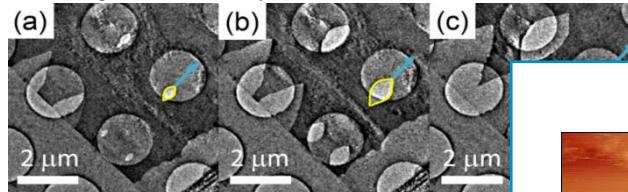
TABLE 1: Measured Surface Lattice Constants and Theoretical Optimized Results Together with Previous Data of Bulk BP

reported by Morita ⁷	measured from STM images	theoretical optimized results
$a = 3.313 \text{ \AA}$	$a = 3.33 \text{ \AA}$	$a = 3.28 \text{ \AA}$
$b = 10.473 \text{ \AA}$	$b = 10.37 \text{ \AA}$	$b = 10.37 \text{ \AA}$
$c = 4.374 \text{ \AA}$	$c = 4.33 \text{ \AA}$	$c = 4.35 \text{ \AA}$
$d_1 = 2.222 \text{ \AA}$, $\alpha_1 = 96.5^\circ$		
$d_2 = 2.777 \text{ \AA}$, $\alpha_2 = 101.9^\circ$		

... and outlooks

Ongoing activity: Controlled desorption of bP

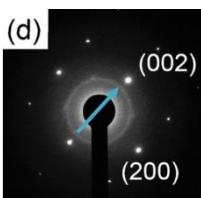
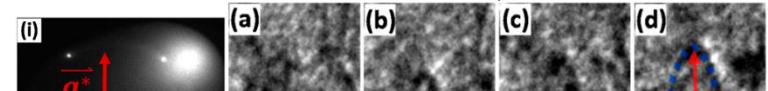
Xiaolong Liu et. al., J. Phys. Chem. Lett. 2015, 6, 773.



TEM image of eye shaped crack opening on
BP flake at 400°C for 5, 8 and 12 min.



M. F. Deschenes et. al., J. Phys. Chem. Lett. 2016, 7, 1667.



After 2h annealing at 400°C

... and outlooks

SEED Project

**SURface properties of few layer black PHOSphorus
investigated by scanning tunnelling microscopy**



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***"Phosphorene functionalization: a new platform
for advanced multifunctional materials"***



Thank you for your attention!

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NEST